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(71)Applicant : GUNZE LTD

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(72)Inventor : OI SHIGEO
OSHIMA HIROSHI
HASHIMOTO SATOSHI

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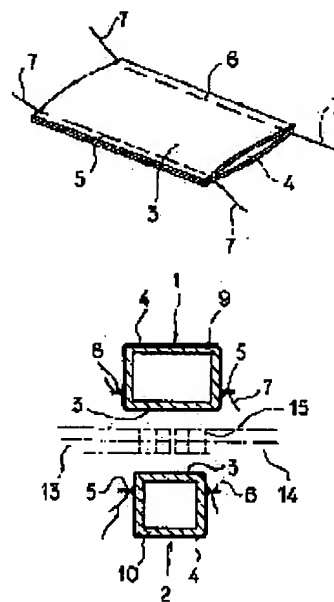
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(54) SUTURE PROSTHETIC MATERIAL

(57)Abstract:

PURPOSE: To facilitate insertion and alignment of a suture prosthetic material adequate for use in an automatic suture device in surgical operation and to solve problems of mispositioning, etc., after mounting by forming a cloth body to a cylindrical shape, thereby forming the prosthetic material described above.

CONSTITUTION: This suture prosthetic material is formed by superposing non-woven fabrics 3 consisting of an in-vivo decomposable absorbent blank and a power net fabric 4 on each other and forming these fabrics to a cylindrical shape by subjecting both edge parts to chain stitching 5, 6. Both ends 7 of the sewing yarn are extended. The in-vivo decomposable absorbent blank includes a polyglycolic acid, polylactic acid, a copolymer of the glycolic acid and lactic acid, paradioxanone, polycarprolactone, chitin, etc. The prosthetic material is mounted to the frame part 10 and cartridge part 9, respectively, of the suture device at the time of use. Both are then integrally fixed by staples in the state of holding the body tissues of the lesion between non-woven fabrics 3, 3 and the lesion 13 is ported. The power net fabric 4 is removed outside the body together with the lesion 13 by pulling the yarn ends 7.



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